



R&D status of Hf-STJ

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For COBAND collaboration

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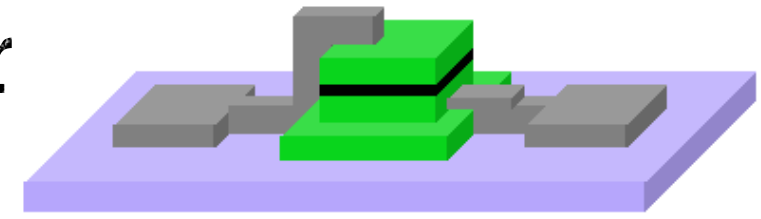
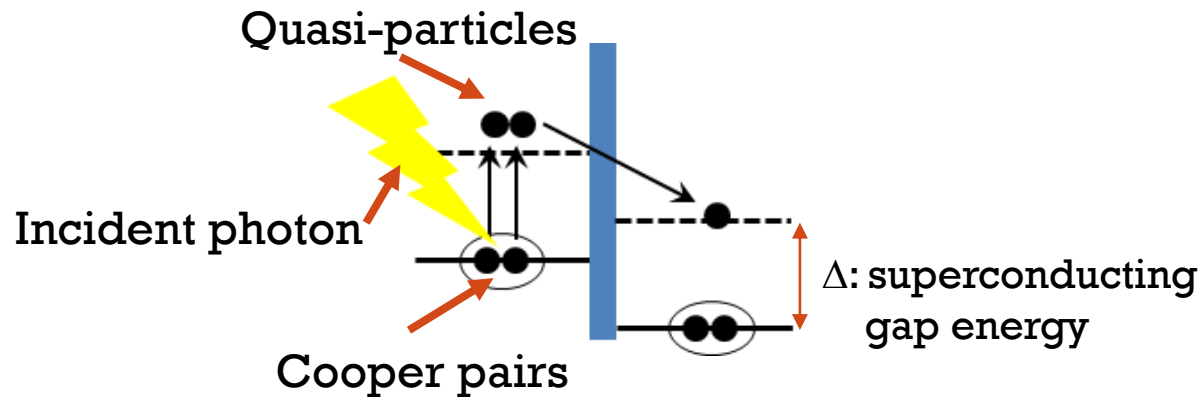
STJ (Superconducting Tunnel Junction) Detector

■ Structure

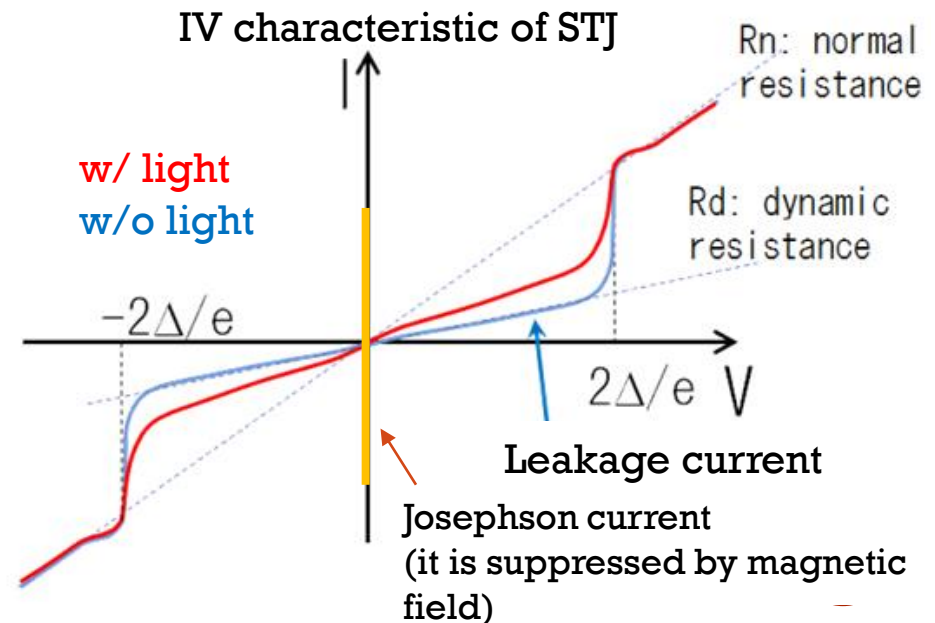
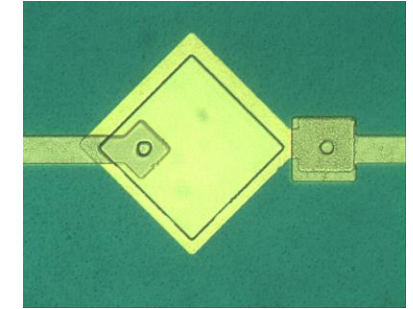
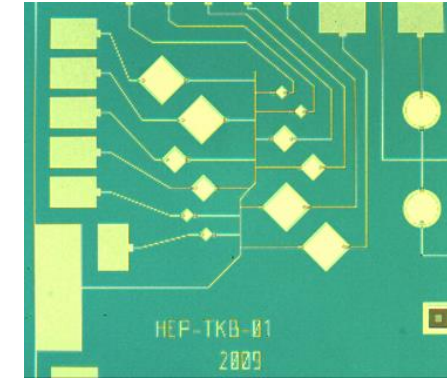
- STJ is a type of Josephson junction composed of Superconductor/Insulator/Superconductor
- Size: dozens ~ hundreds μm square and 500 nm height

■ Working principle

- Incident photon is absorbed in the superconductor and excites cooper pairs.
- Excited cooper pairs become quasi-particles.
- Quasi-particles go through insulator by tunnel effect.
- Number of quasi-particles is determined by energy of incident particle.
- Thus, we can measure the energy of incident particle by measuring the tunnel current.



Overhead view of STJ detector



Energy resolution of STJ detector

- Statistical fluctuation in the number of quasi-particles determines the STJ energy resolution.
- Smaller superconducting gap energy Δ yields better energy resolution.

$$\sigma_E/E = \sqrt{(1.7\Delta)F/E}$$

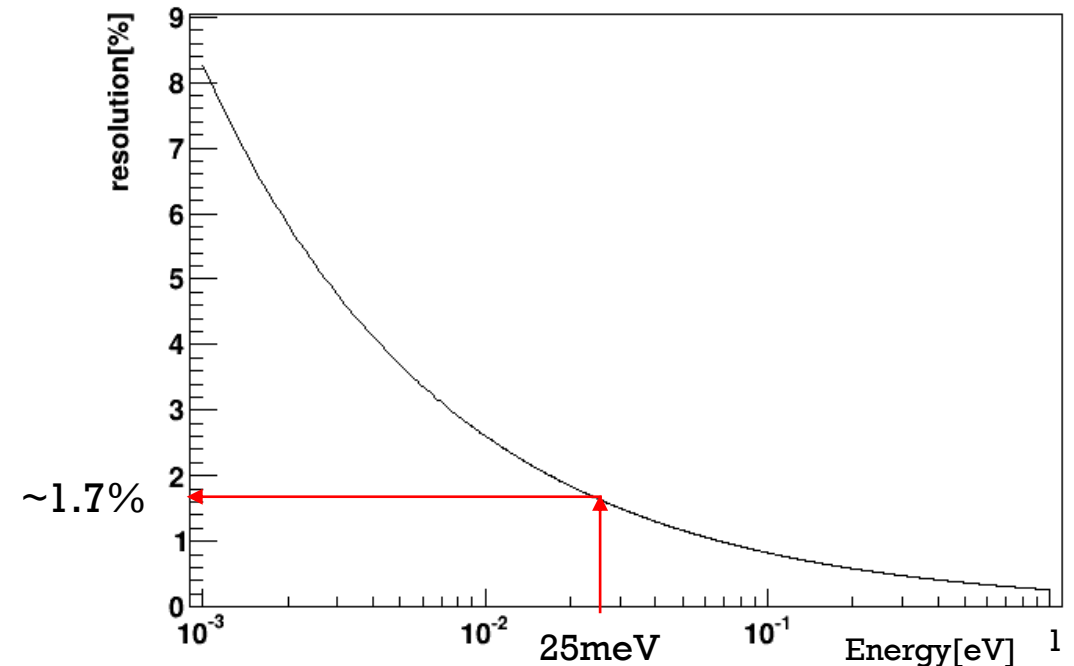
Δ : Superconducting gap energy
 F : fano factor
 ϵ : Photon energy

Material	Tc(K)	Δ (meV)
Niobium	9.20	1.550
Aluminum	1.14	0.172
Hafnium	0.13	0.021

Tc : Superconducting critical temperature
Need $\sim 1/10T_c$ for practical operation

- Hf-STJ as a photon detector is not established
- $N_{q.p.} = 25\text{meV}/1.7\Delta = 735$
- 2% energy resolution is achievable because Δ_{Hf} is very small.

Expected energy resolution of Hf-STJ ($F=0.2$)



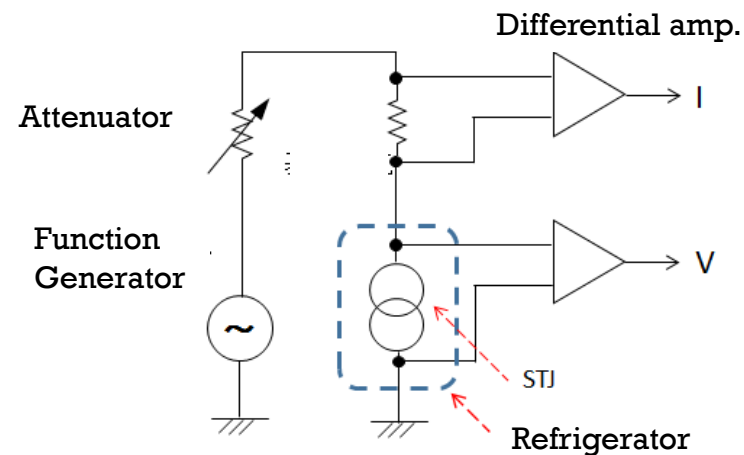
Development environment

Production:

- Hf-STJ is produced in a clean room at KEK
 - Thin-film formation using magnetron sputter
 - Patterning with photolithography process
 - Dry etching using ICP-RIE
 - Thermal oxidation

Measurement:

- measure IV characteristic and light response.
- $T \sim 120\text{mK}$ using a dilution refrigerator.
 - This refrigerator could provide 15 mK.
 - Now it is out of condition, achieving temperature is $\sim 120\text{mK}$



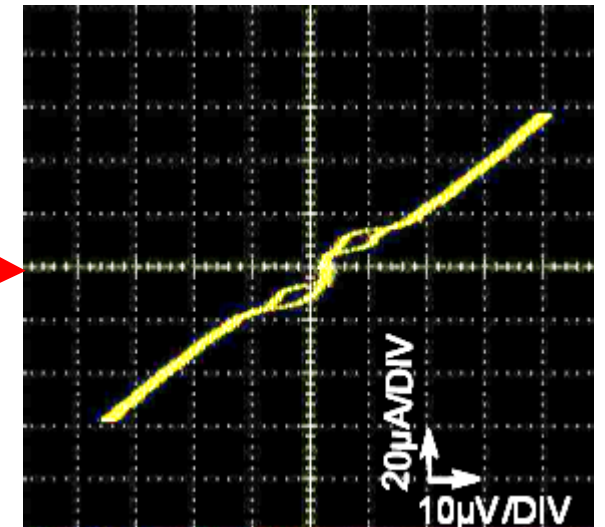
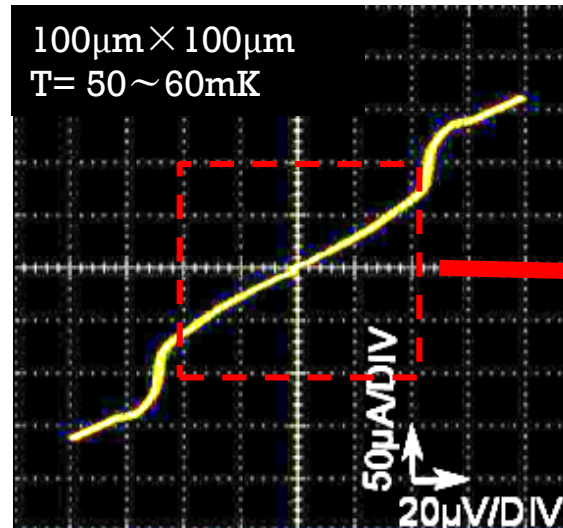
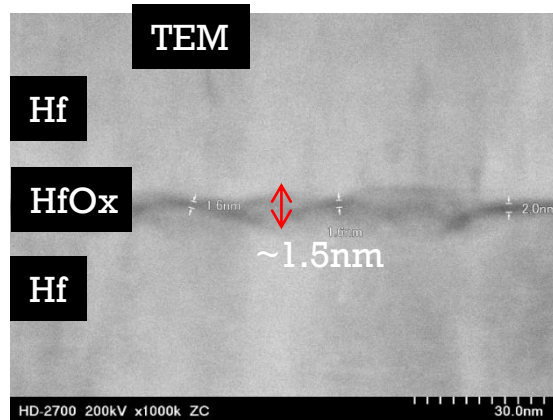
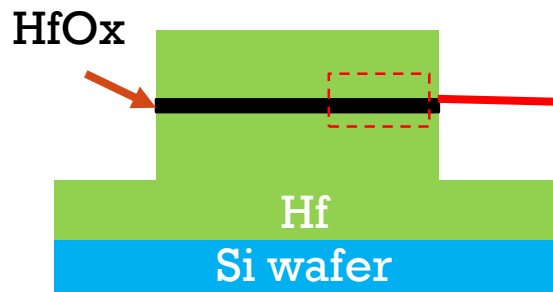
Earlier version of Hf-STJ

- Earlier version of our Hf-STJ
 - Structure: Hf/HfO_x/Hf = 250nm/1.5nm/300nm
 - $\Delta \sim 20\mu\text{eV}$
 - Leakage current $\sim 20\mu\text{A}@50\text{mK}$, $20\mu\text{V}$ ($100\mu\text{m} \times 100\mu\text{m}$ sample)

Leakage current is too large.

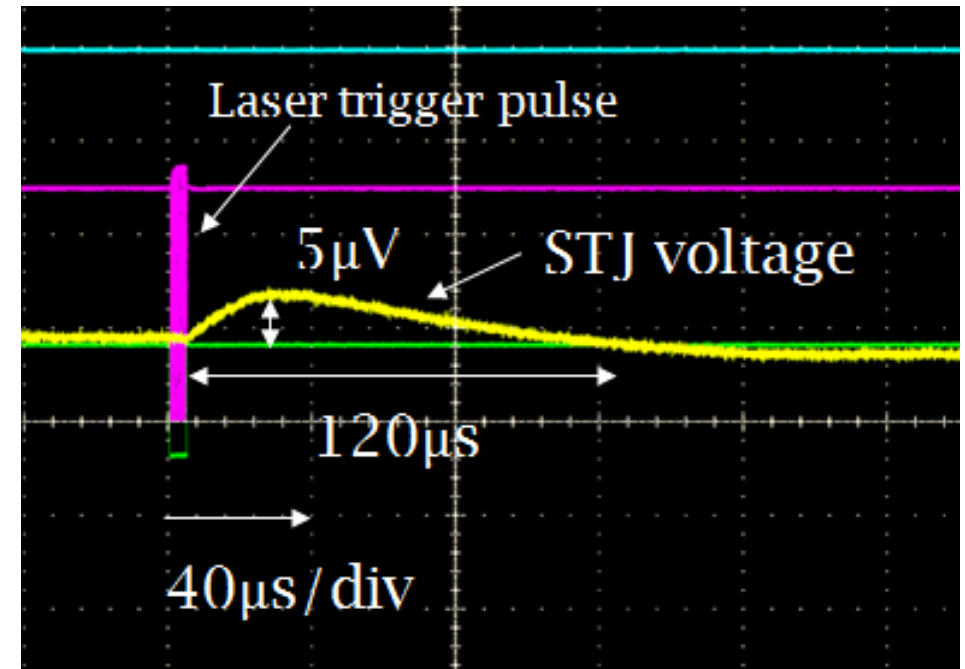
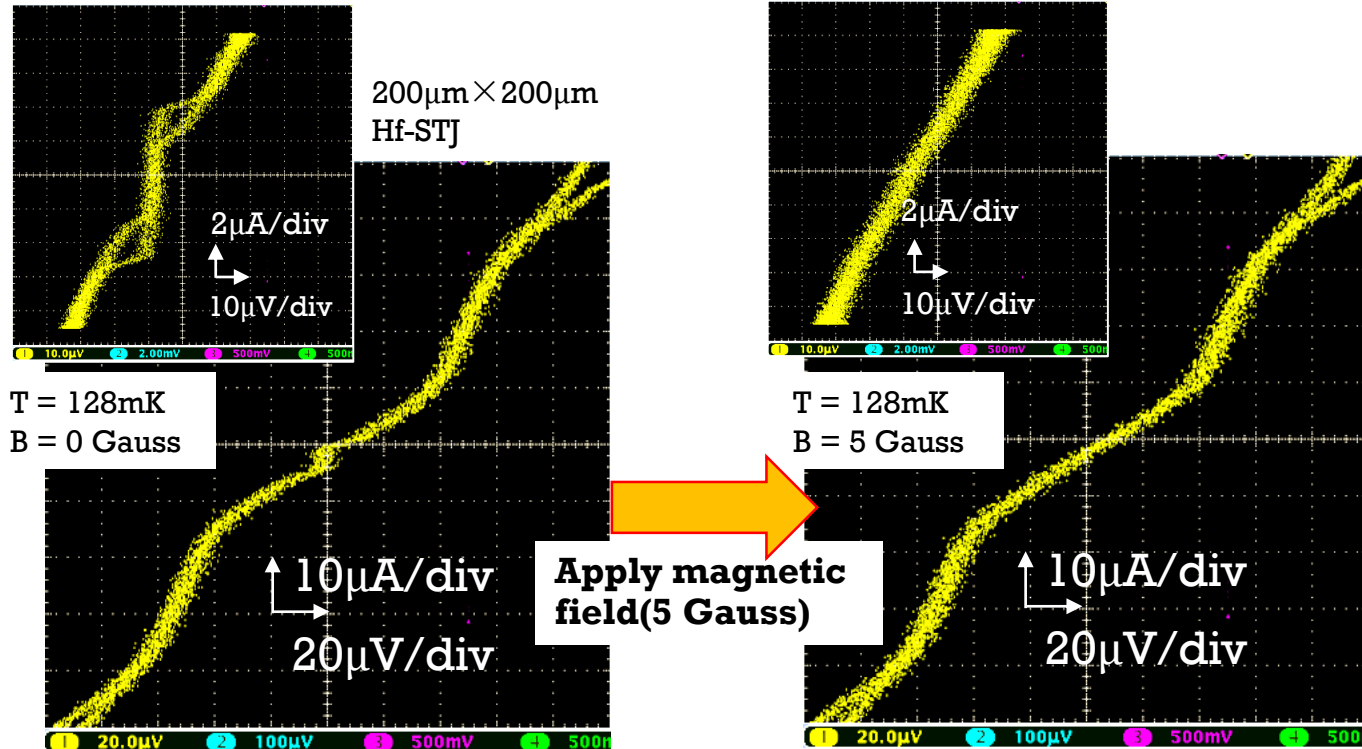
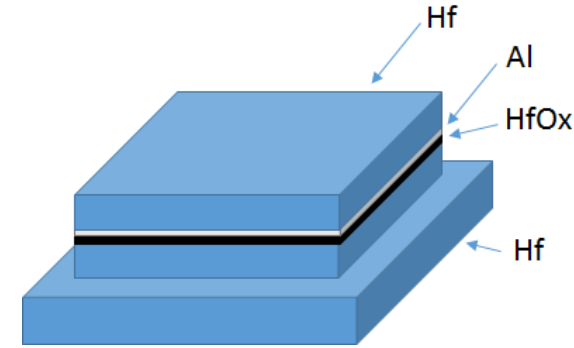
Required leakage current = $10\text{pA}@50\text{mK}$

Necessary to perform improvements very much.



Earlier version of Hf-STJ (Hf-STJ w/ thin Al layer)

- We made another type of Hf-STJ.
- We add thin (a few nm) Al layer between the insulator and the upper Hf layer.
 - Josephson current is observed and it's suppressed by magnetic field.
 - $\Delta = 20\sim 30\mu\text{eV}$.
 - $I_{\text{leak}} = 5\mu\text{A}@128\text{mK}$ ($200\mu\text{m} \times 200\mu\text{m}$ sample)
 - **Response to visible laser pulses is observed.**
 - But leakage current is still large. Need more improvement.

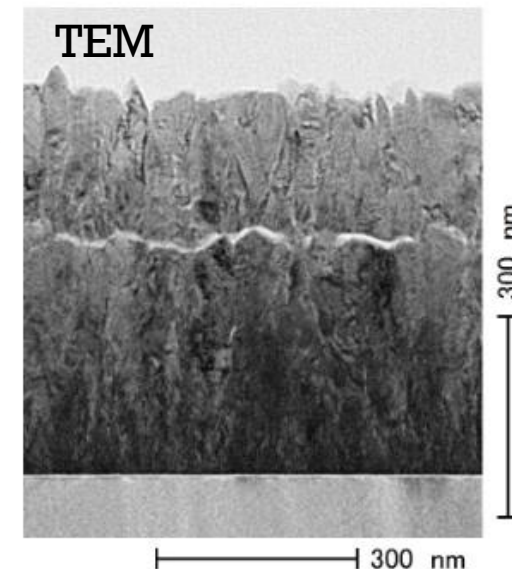


Response to laser pulses

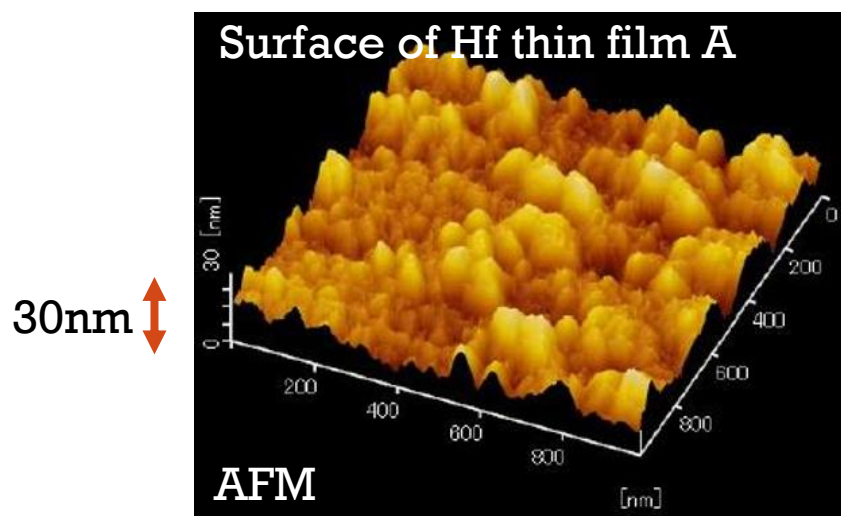
- $\lambda = 465\text{nm}$

Improvement of surface roughness of Hf thin film

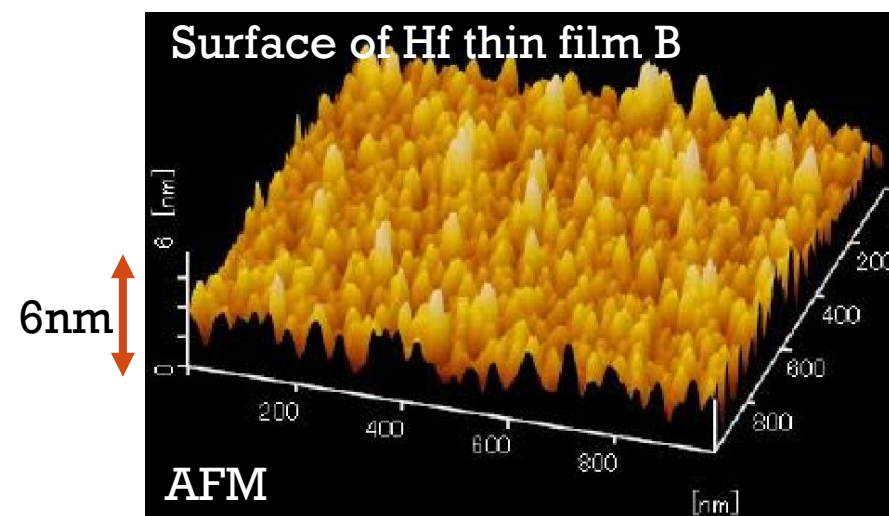
- Hf surfaces of earlier Hf-STJs are very rough.
- Rough surfaces of Hf layer cause defects of insulator.
- To reduce leakage current, we modified the sputtering condition to make smooth Hf layers.
- Target value of RMS of surface roughness $< 1\text{nm}$.
 - RMS should be smaller than thickness of HfOx ($\sim 1.5\text{nm}$).



Sputtering condition A: Ar 2.0Pa, 70W
RMS of surface roughness = 2.5 nm



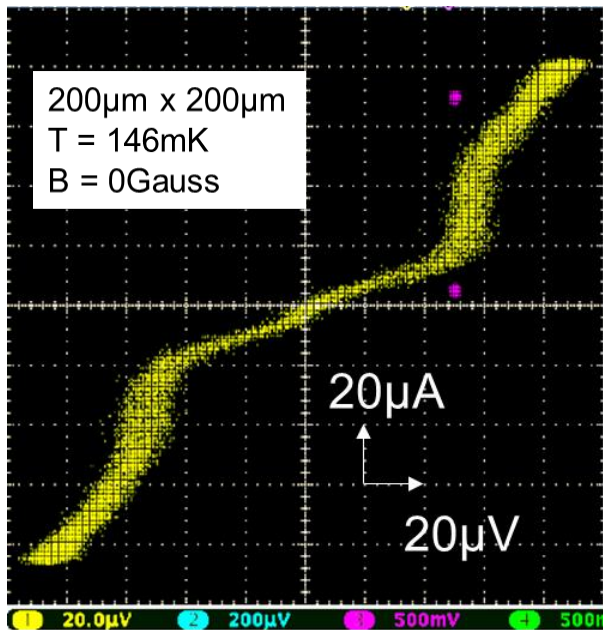
Sputtering condition B: Ar 0.5Pa, 50W
RMS of surface roughness = 0.96 nm



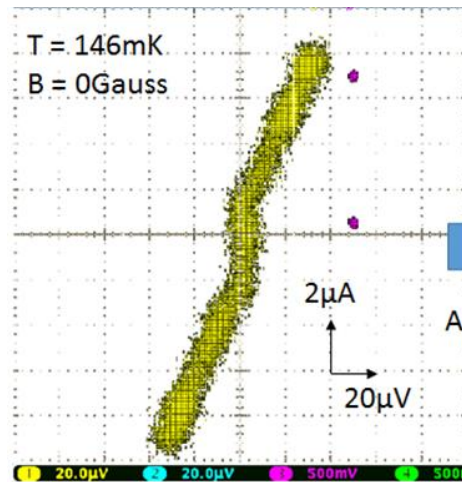
We made Hf-STJs using these Hf thin films.

Hf-STJ using sputtering condition A (RMS=2.5nm)

- Josephson current is observed ($\sim 2\mu\text{A}$). But very small.
- $\Delta \sim 25\mu\text{eV}$.
- Leakage current: $7\mu\text{A}@20\mu\text{V}$
 - 3 times smaller than old Hf-STJ. Improved but still large.
- Response to visible light is observed. $7\mu\text{A}$ increase by light illumination.



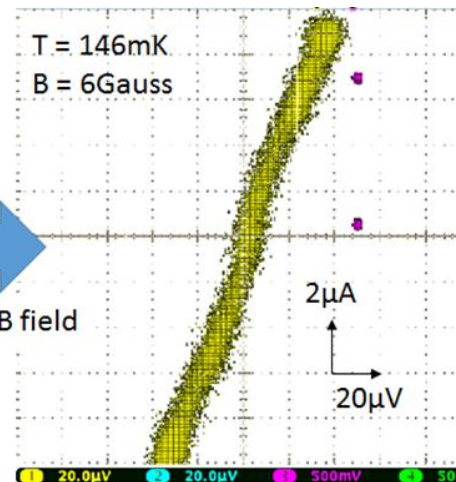
IV characteristic



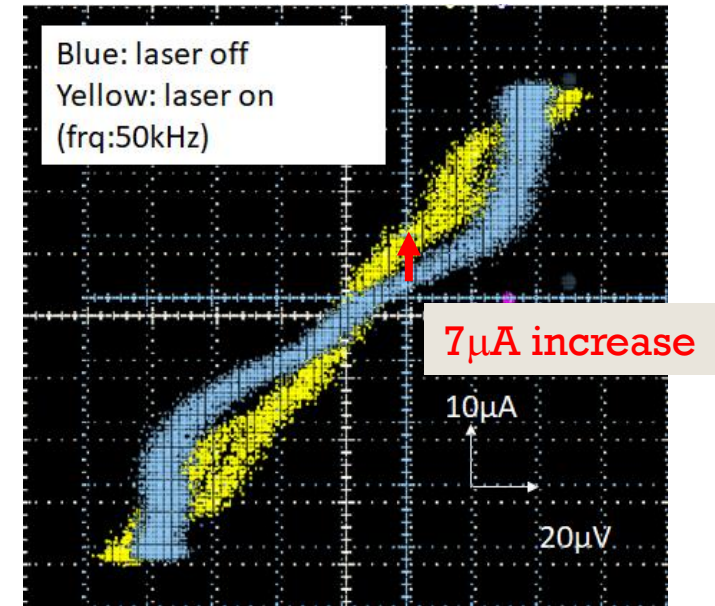
IV characteristic
(near 0V, B=0Gauss)



Apply B field



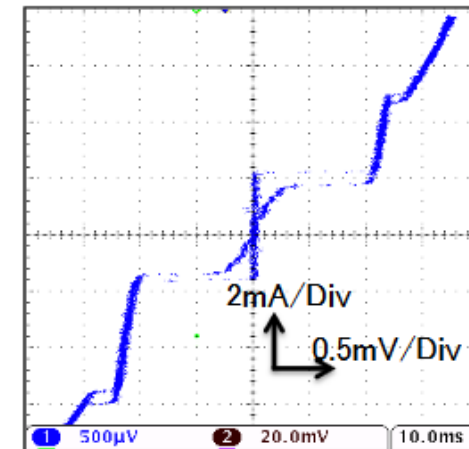
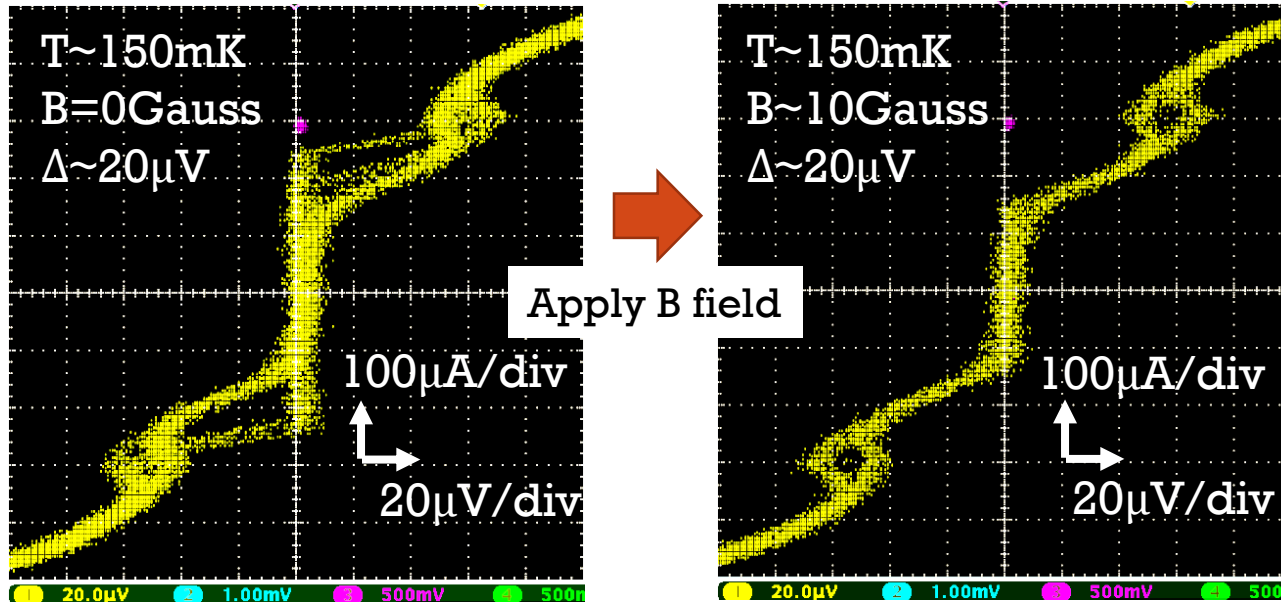
IV characteristic
(near 0V, 6Gauss)



Response to visible($\lambda=465\text{nm}$) DC-like laser light
T = 140mK, 9Gauss B field is applied.

Hf-STJ using sputtering condition B (RMS=0.96nm)

- Josephson current is observed: $\sim 250\mu\text{A}$
- $\Delta \sim 25\mu\text{eV}$
- Leakage current: $\sim 170\mu\text{A}@20\mu\text{V}$
- This Hf-STJ has a shape of IV curve similar to Nb/Al-STJ with insufficient cooling.
- This IV curve is measured at near T_c of Hf. Therefore it has large thermal leakage current.
- If we measure this Hf-STJ at below $0.1T_c$, this sample may show a good performance.



IV characteristic of Nb/Al-STJ
@ 3K, B field does not applied.

Improvement plan

- Keep doing the optimization of sputtering condition of Hf film.
- Down sizing
 - Size of previous Hf-STJ is 200um x 200um.
 - We will make 10um x 10um junction
 - 400 times improvement of leakage current is expected.
- Fix a dilution refrigerator to make cryogenic temperature below 50mK.
 - Reduce thermal leakage current of Hf-STJ.

Summary

- We are developing Hf-STJ detector to detect a single far-infrared photon in energy range between 15 and 30meV for the COBAND satellite experiment.
- Leakage current of Hf-STJ is improved and Hf-STJ response to the visible light was observed.
- However, Hf-STJ hasn't exhibited an enough performance for the COBAND experiment due to it's large leakage current.
- Improvement is underway.

Thank you for your attention.